EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S1	3	("4305817").PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/07/12 10:36
S2	2	("4305917").PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/07/12 10:37
S3	5	"4305917"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/07/12 10:37
S4	3	"04305917"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/07/12 10:41
S5	6	(("20050052632") or ("20050219489") or ("20050200815")).PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/07/12 10:47
S6	2	("5610683").PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/07/12 10:47
S7	1262	(250/548).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/07/12 13:05
S10	177	S7 and lithograph$3 and liquid	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/07/12 15:24

S11	24	(("4390273") or ("6603130") or ("6633365") or ("20020163629") or ("20030123040") or ("20030174408") or ("20040075895") or ("20040109237") or ("6236634") or ("20020020821") or ("20040119954") or ("20040125351")).PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/07/12 14:16
S13	685	immersion with lithograph$3 and (align$4 mark) and liquid	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/07/12 15:32
S14	189	immersion with lithograph$3 and (align$4 mark) and liquid not asml. as.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/07/13 10:59
S15	496	S13 not S14	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/07/12 15:33
S16	345	(250/559.3).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/07/13 07:26
S17	51	S16 and lithograph$3	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/07/13 07:43
S18	1262	(250/548).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/07/13 10:46
S19	797	S18 and align$5	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/07/13 07:54

S20	348	S18 and align$5 with mark with (wafer substrate)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/07/13 08:21
S21	8	S18 and align$5 with (wafer substrate) near2 relative near2 (stage table)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/07/13 08:23
S22	45	S18 and align$5 with (wafer substrate) near2 (wafer substrate) adj (stage table)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/07/13 08:24
S23	32	S18 and align$5 near2 (wafer substrate) near2 (wafer substrate) adj (stage table)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/07/13 08:26
S24	44	S18 and align$5 near2 (wafer substrate) near2 ("wafer stage" "wafer table" "substrate stage" "substrate table")	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/07/13 08:46
S25	7	S18 and (wafer substrate) adj2 align$5 adj2 ("wafer stage" "wafer table" "substrate stage" "substrate table")	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/07/13 08:48
S26	79	lithograph$3 and (wafer substrate) adj2 align$5 adj2 ("wafer stage" "wafer table" "substrate stage" "substrate table") not S25	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/07/13 09:35
S27	146	lithograph$3 and (wafer substrate) near2 align$5 near2 chuck	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/07/13 09:33

S28	124	lithograph$3 and (wafer substrate) near2 align$5 near2 chuck not asml.as.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/07/13 09:33
S29	22	lithograph$3 and (wafer substrate) adj2 align$5 adj2 chuck	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/07/13 10:01
S30	4	"10303114"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/07/13 10:17
S31	2	("5825043").PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/07/13 10:23
S32	4228	(355/53).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/07/13 10:23
S33	361	S32 and immersion and align$4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/07/13 10:24
S34	100	S32 and immersion and align$4 not asml.as.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/07/13 10:40
S35	66	lithograph$3 and immersion and align$4 with separate not asml.as.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/07/13 10:41

S36	191	immersion with lithograph$3 and (align$4 mark) and liquid not asml. as.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/07/13 10:59
S37	65	immersion with lithograph$3 and (align$4 mark) not asml.as. not S36	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/07/13 10:59
S38	27	(US-20060103832-$ or US-20060033894-$ or US-20060023186-$ or US-20050052632-$ or US-20050219489-$ or US-20050200815-$ or US-20050088633-$ or US-20050007572-$ or US-20050007567-$ or US-20030123040-$ or US-20040119970-$ or US-20020163629-$ or US-20040125351-$ or US-20040075895-$ or US-20020020821-$ or US-20040119954-$ or US-20040109237-$ or US-20040036849-$ or US-20020175300-$ or US-20020015140-$).did. or (US-6603130-$ or US-6236634-$ or US-6498352-$ or US-RE36730-$ or US-6521900-$).did. or (JP-04305917-$ or JP-10303114-$).did.	US-PGPUB; USPAT; JPO	OR	ON	2006/07/13 11:50
S39	1	S38 and level adj sensor	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/07/13 11:50
S40	14	S38 and level	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/07/13 12:44

S41	403	lithograph$3 and level adj sensor	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/07/13 12:46
S42	304	lithograph$3 and level adj sensor not asml.as.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/07/13 12:53
S43	8	lithograph$3 and level adj sensor and (wafer substrate) near2 map$4 not asml.as.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/07/13 12:55
S44	44	lithograph$3 and tilt and (wafer substrate) near2 map$4 not asml. as.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/07/13 13:03
S45	15	lithograph$3 and tilt and (wafer substrate) near2 map$4 near3 height not asml.as.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/07/13 13:03